

FIG. 1

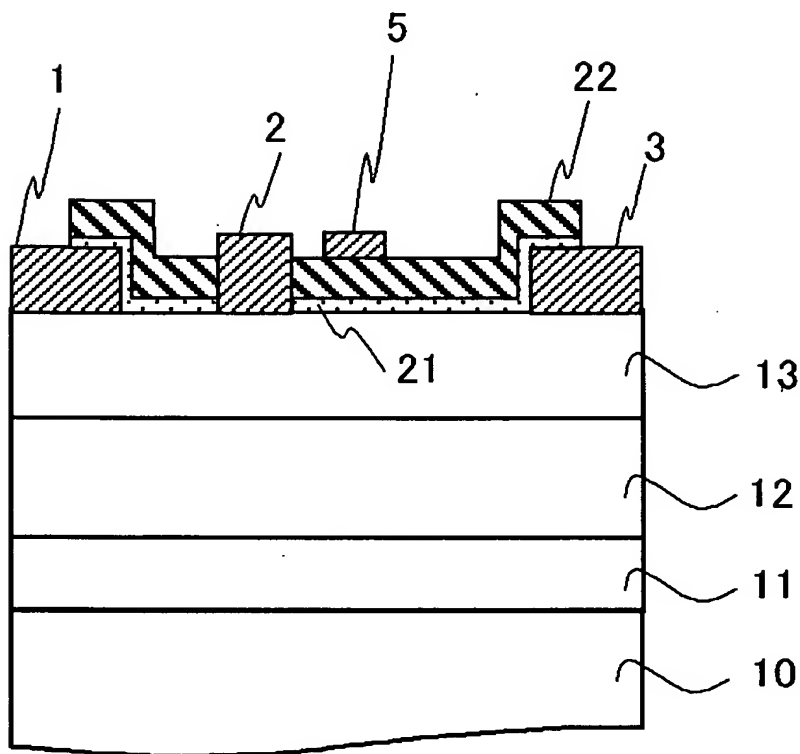


FIG. 2

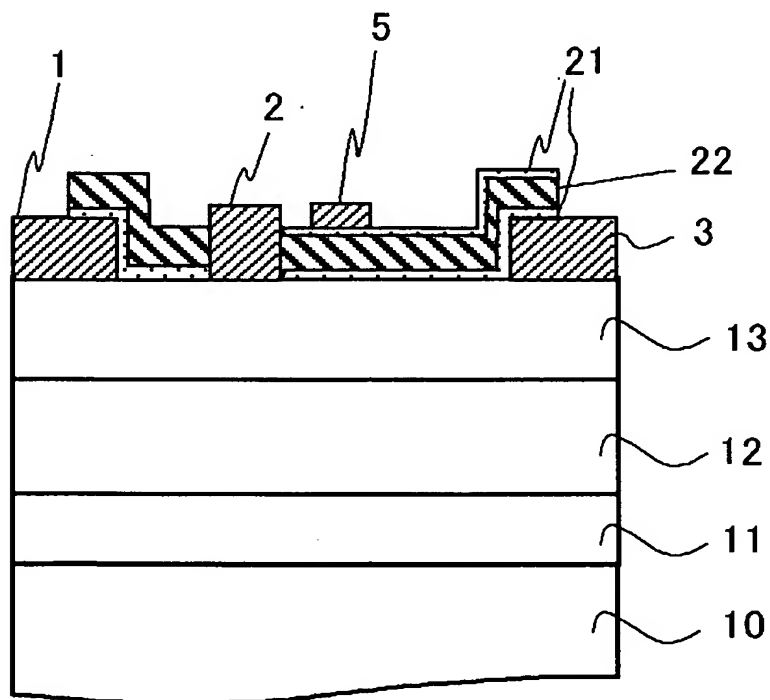


FIG. 3

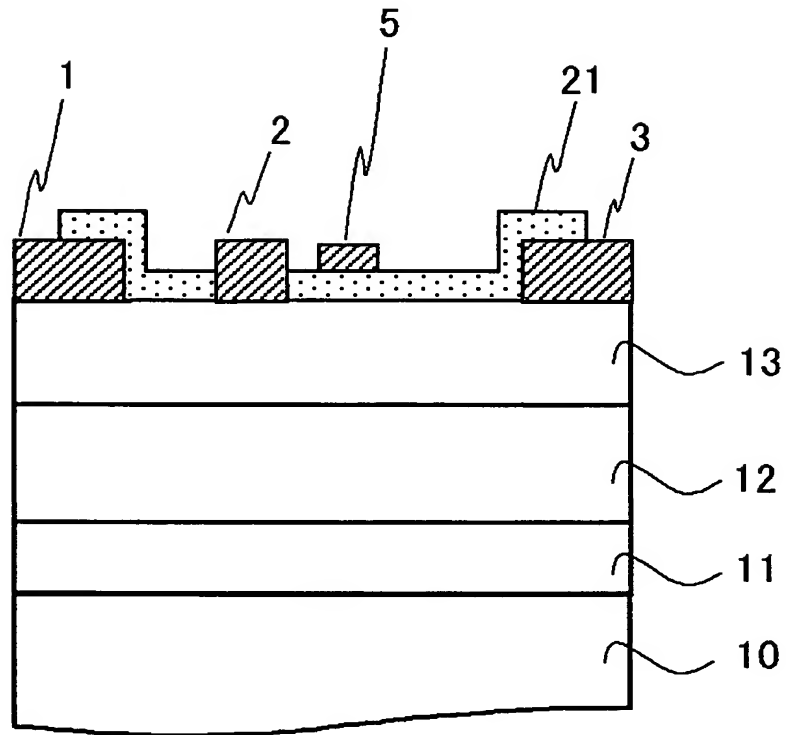
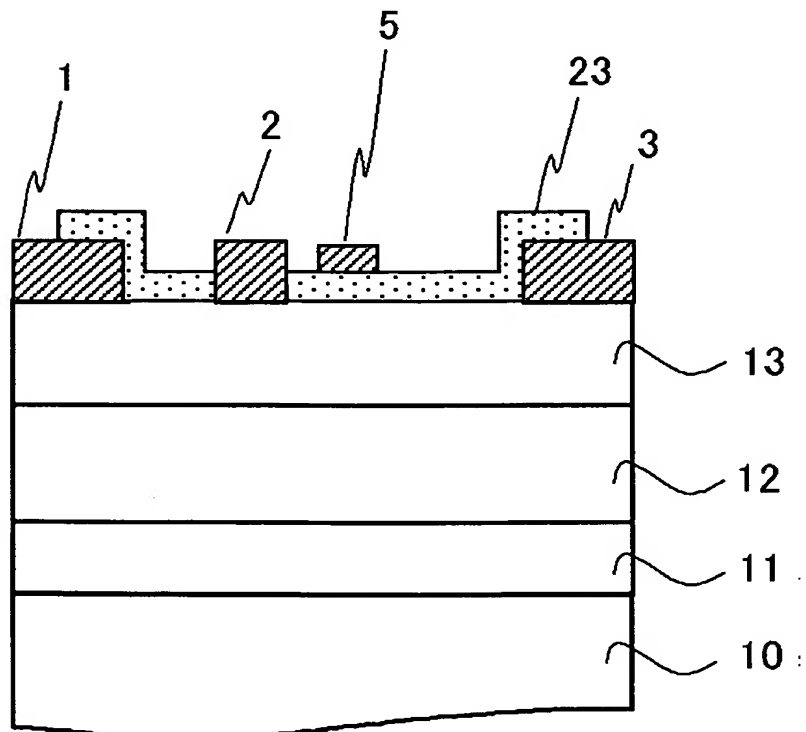


FIG. 4



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FIG. 5

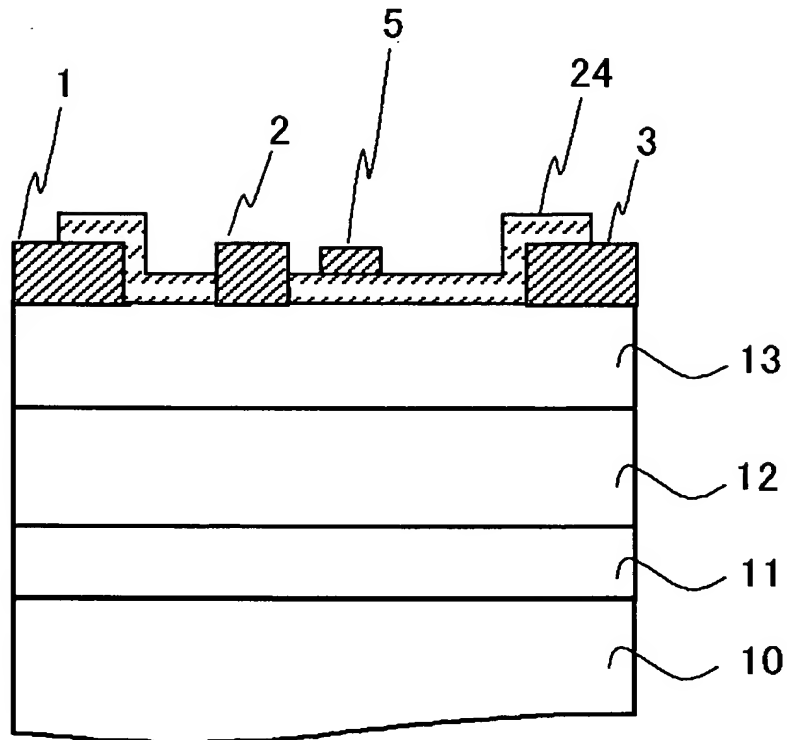
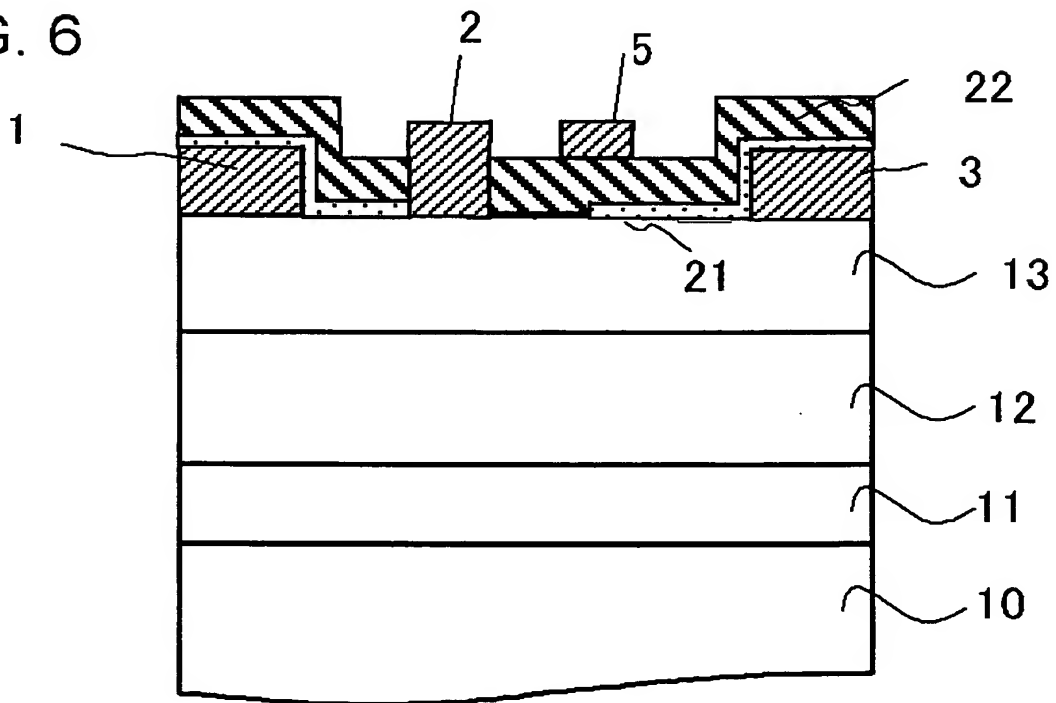
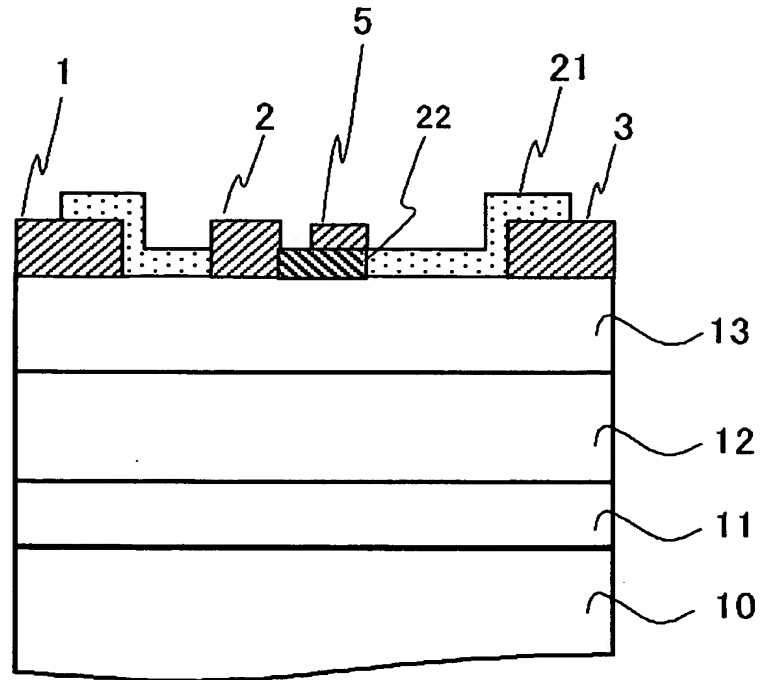


FIG. 6

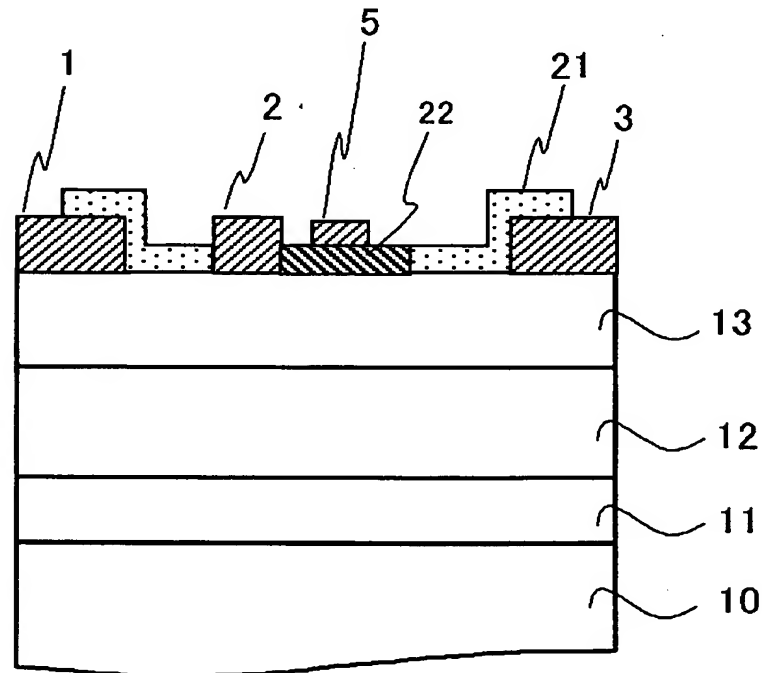


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FIG. 7  
(a)

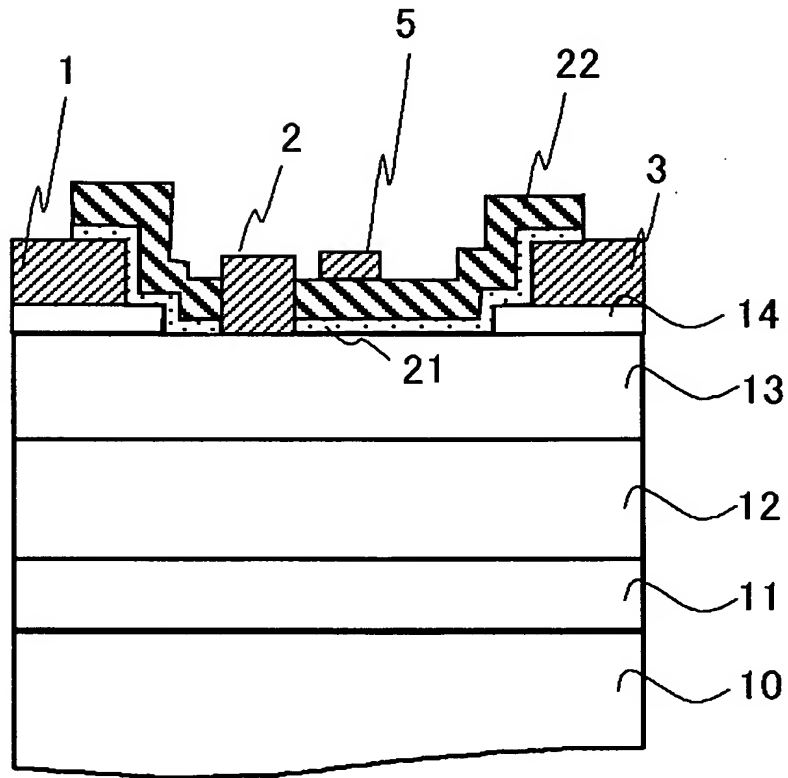


(b)



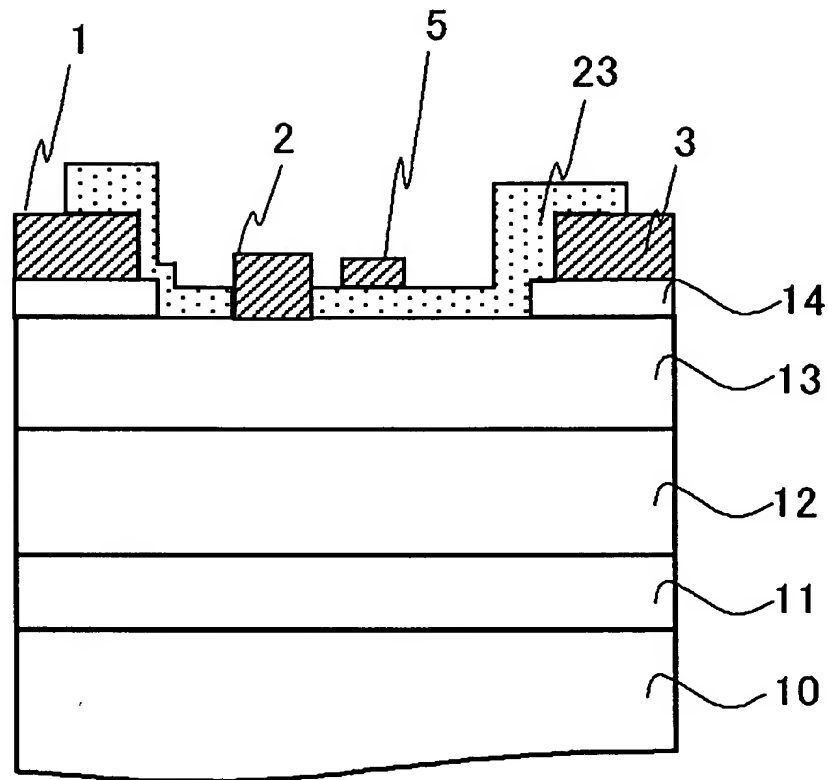
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FIG. 8



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FIG. 9



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FIG. 10

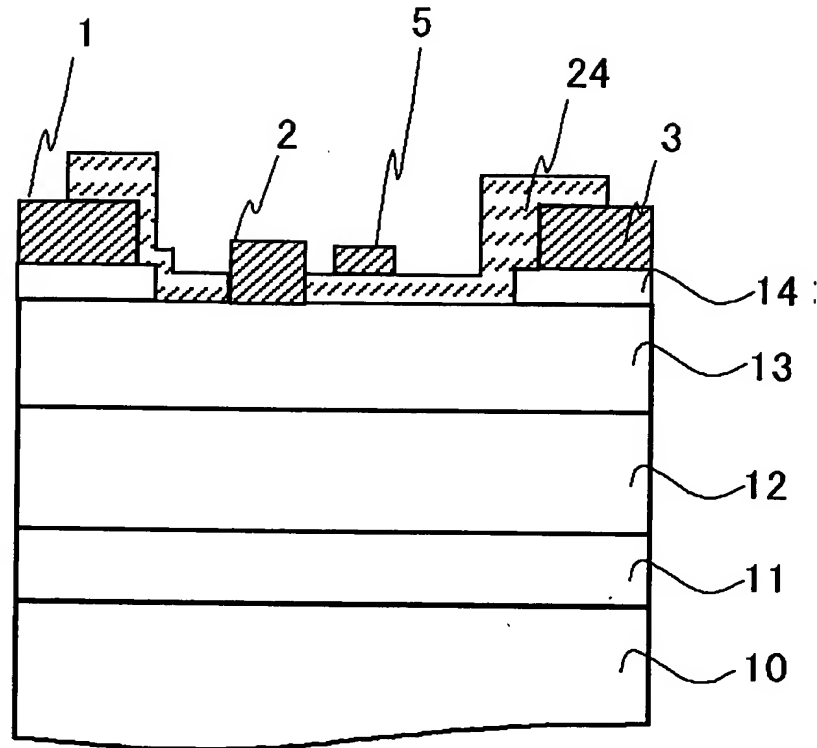
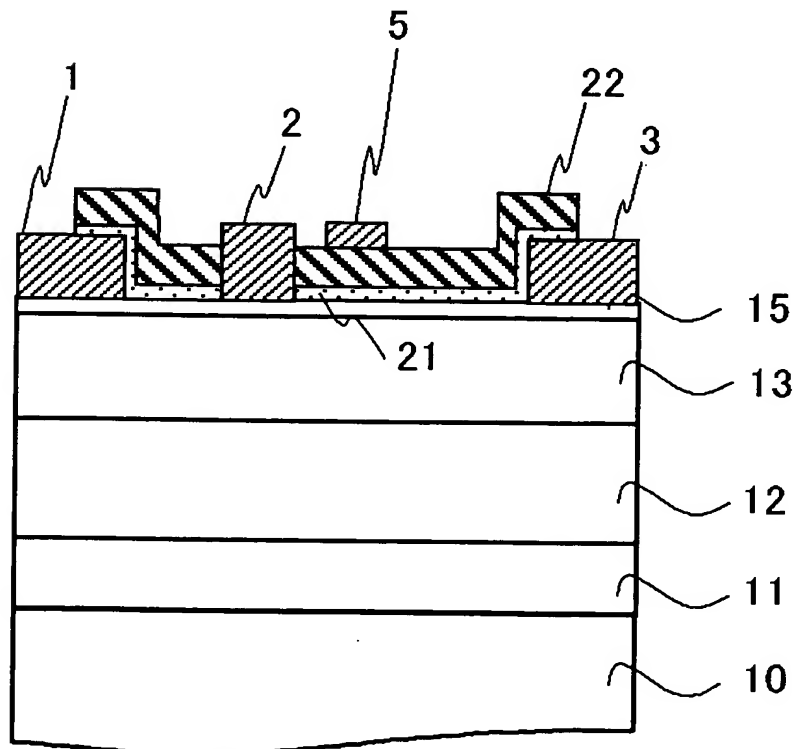
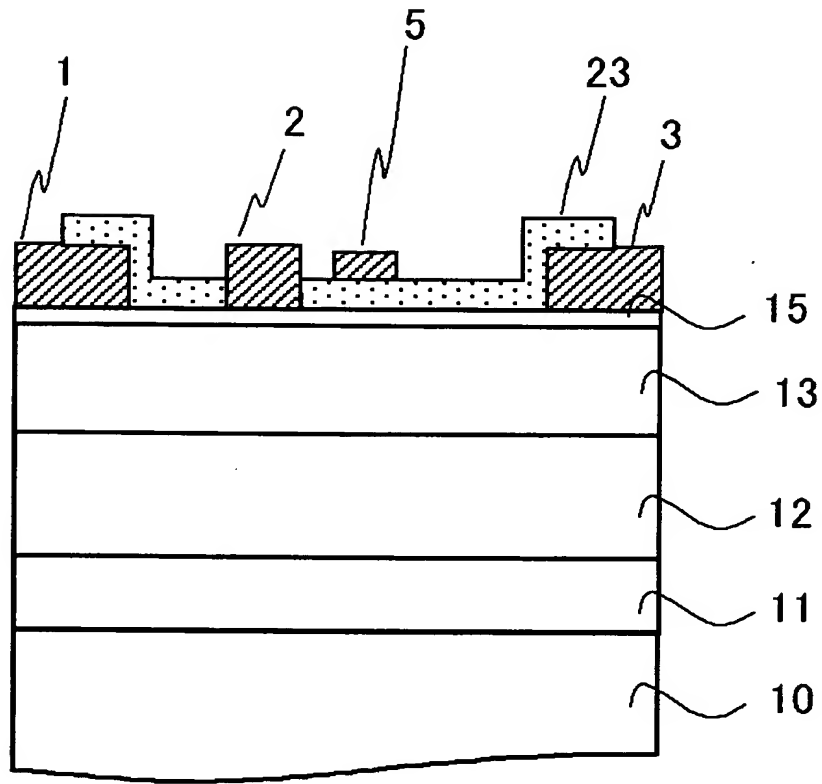


FIG. 11



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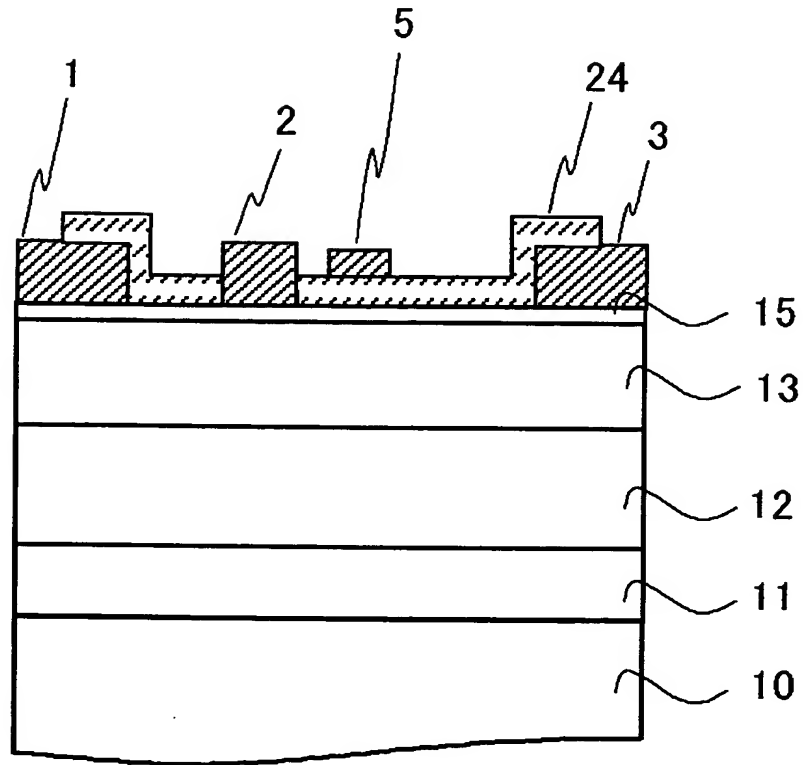
FIG. 12





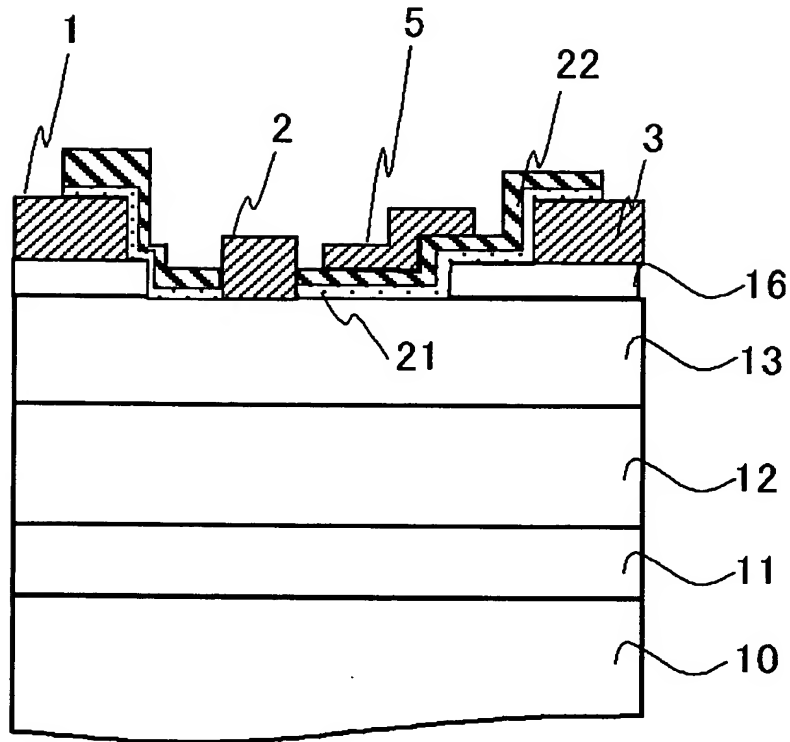
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FIG. 13



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FIG. 14

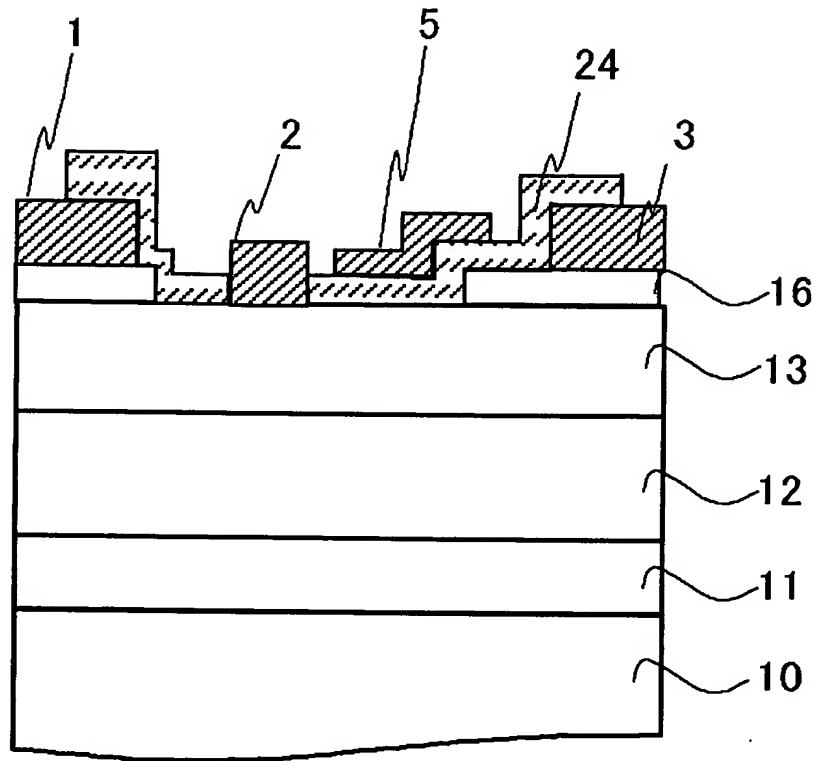


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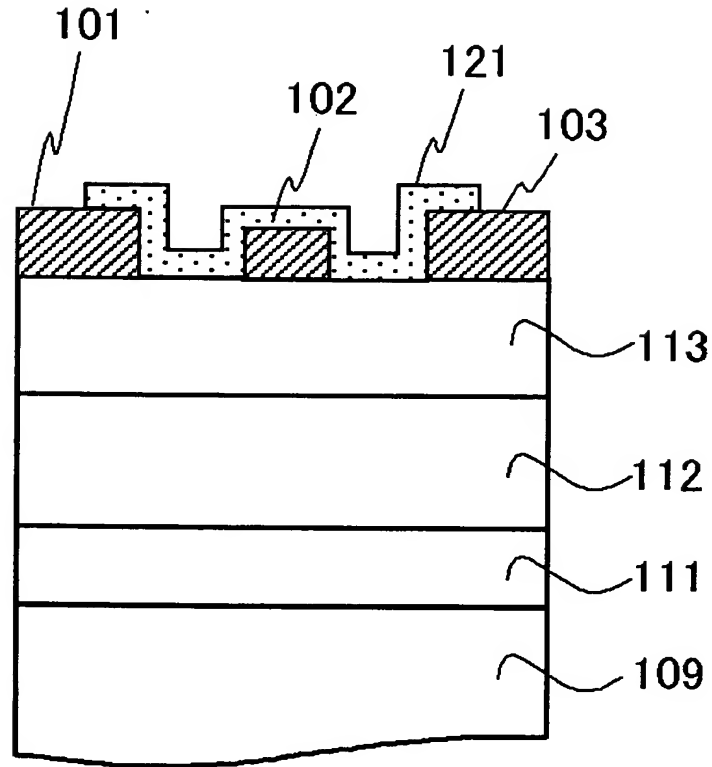
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FIG. 16



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FIG. 17



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FIG. 18

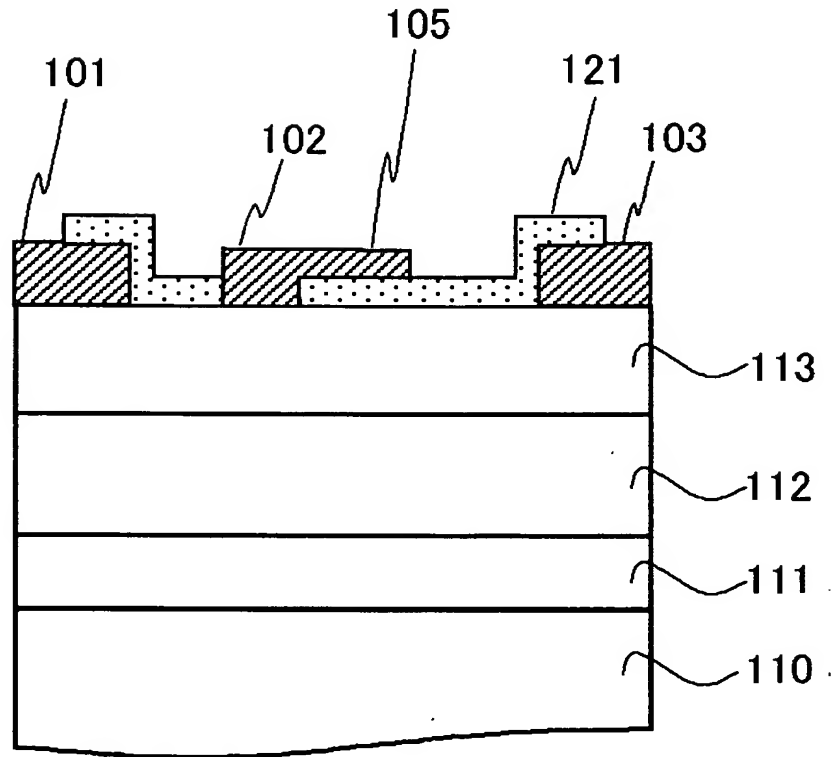


FIG. 19

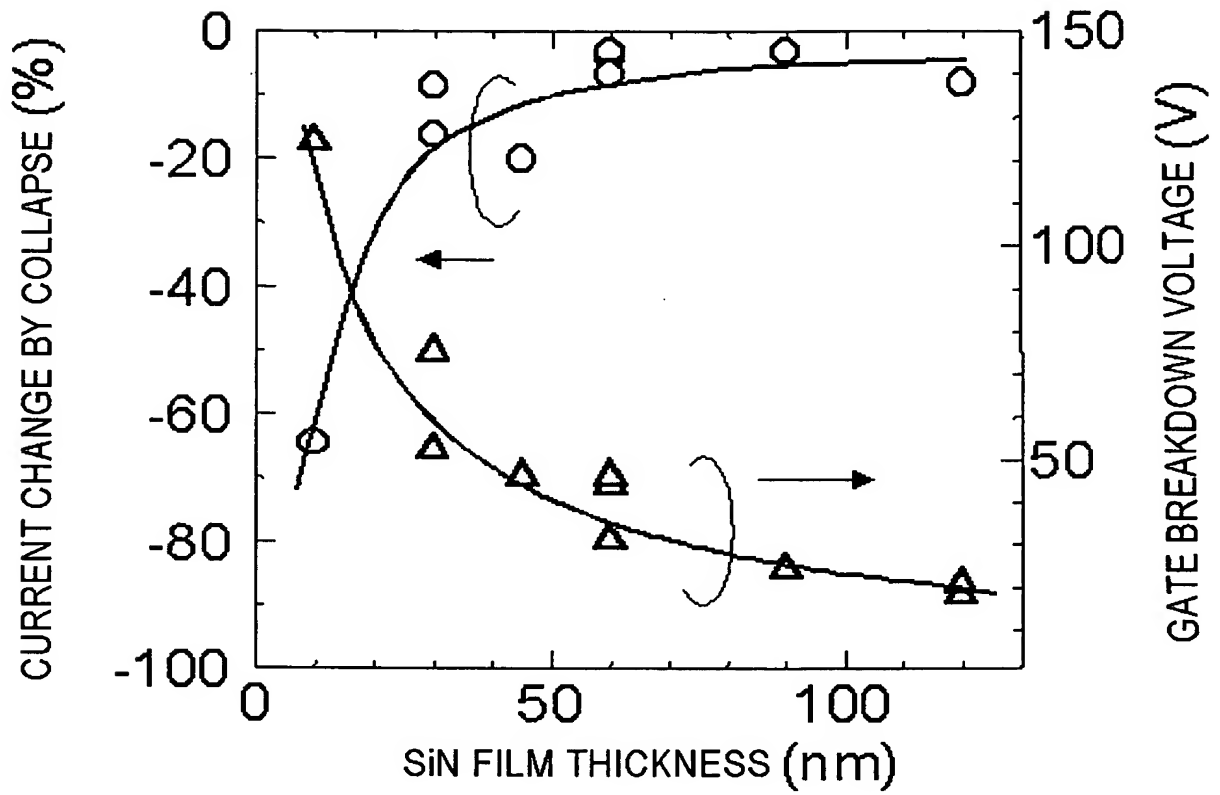
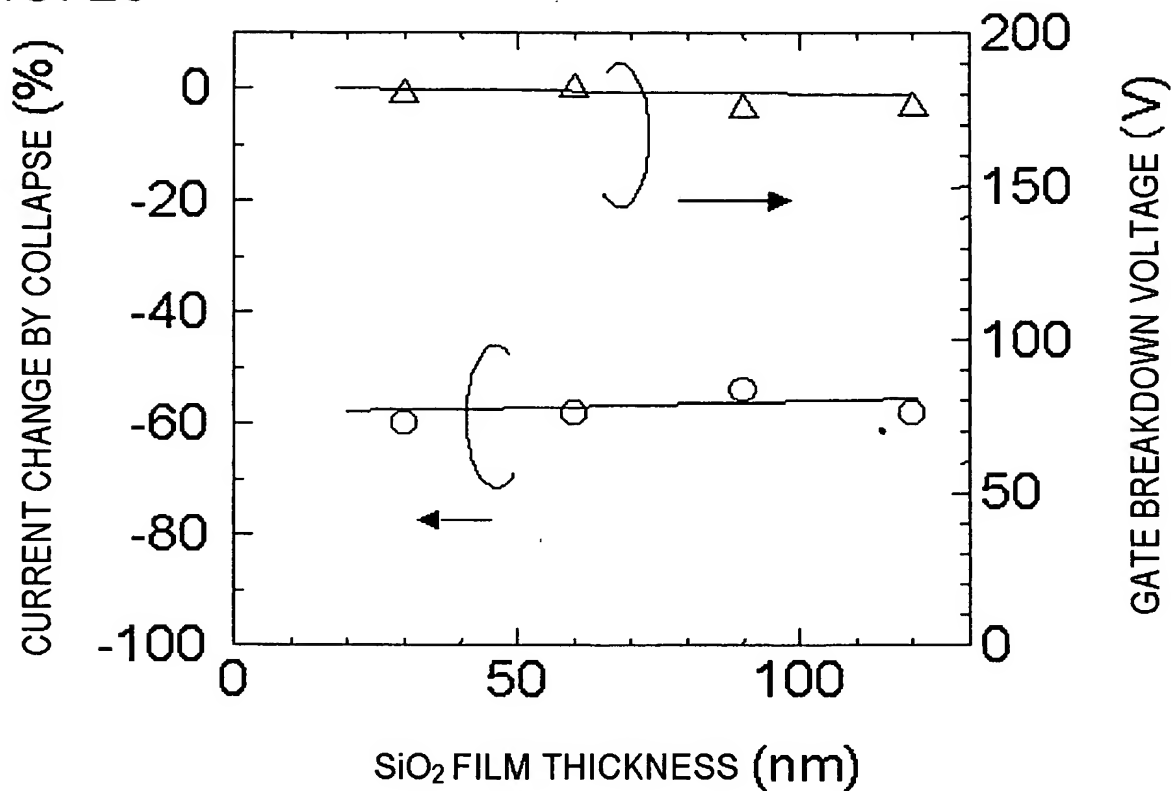


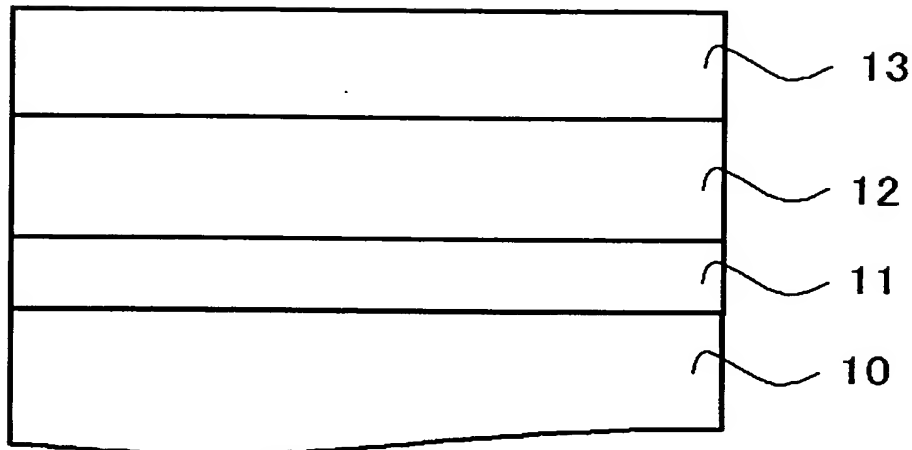
FIG. 20



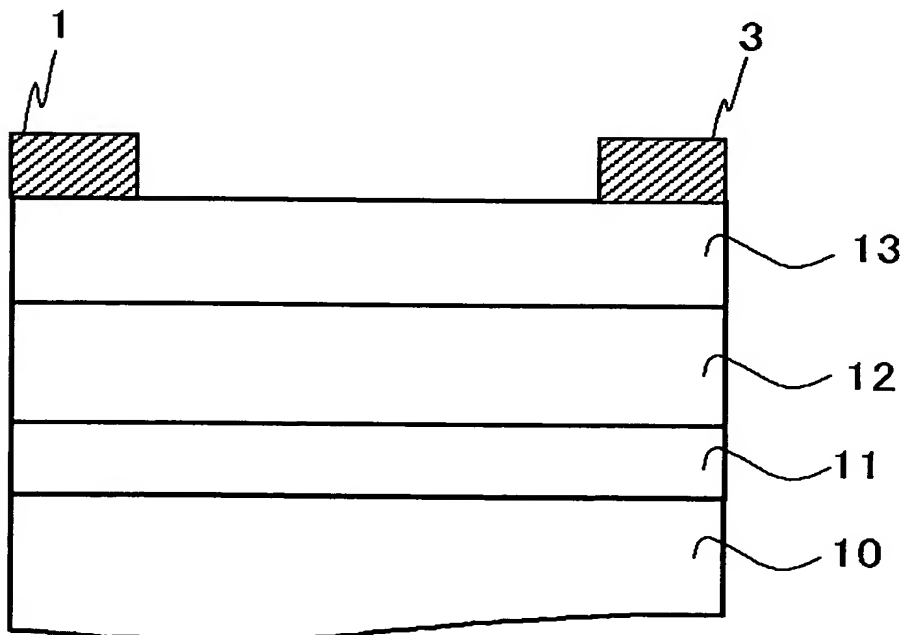


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FIG. 21



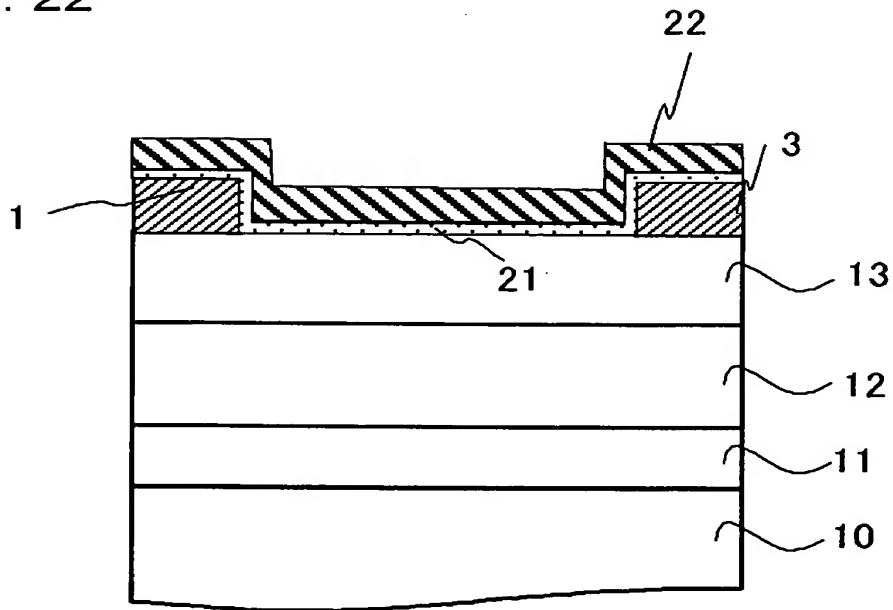
(a)



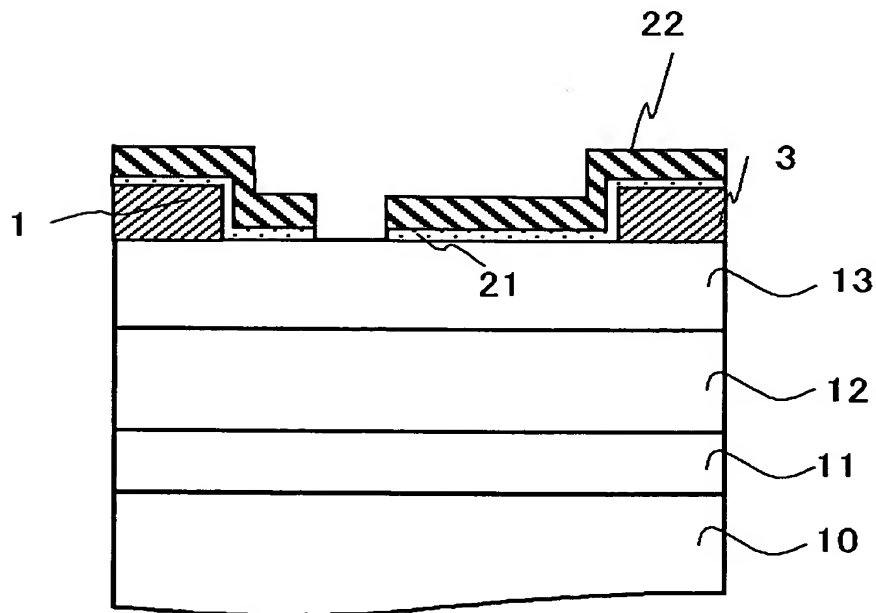
(b)

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FIG. 22

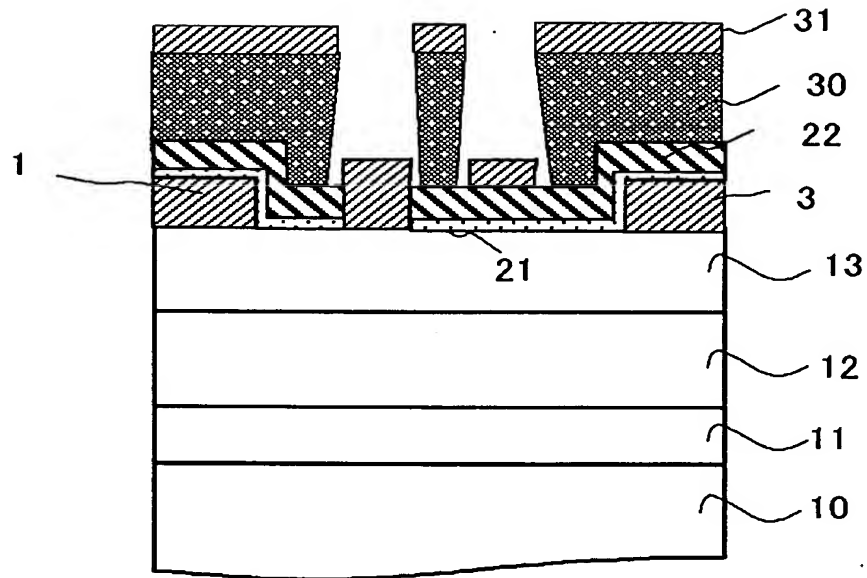


(c)

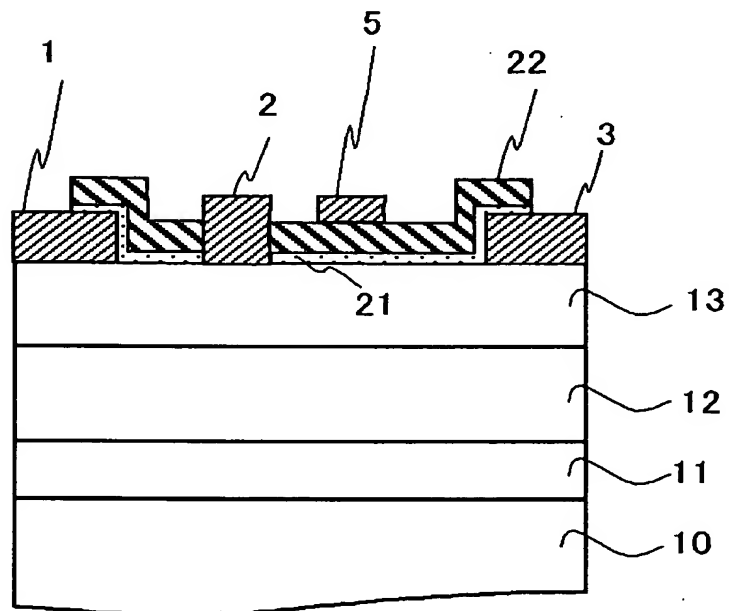


(d)

FIG. 23



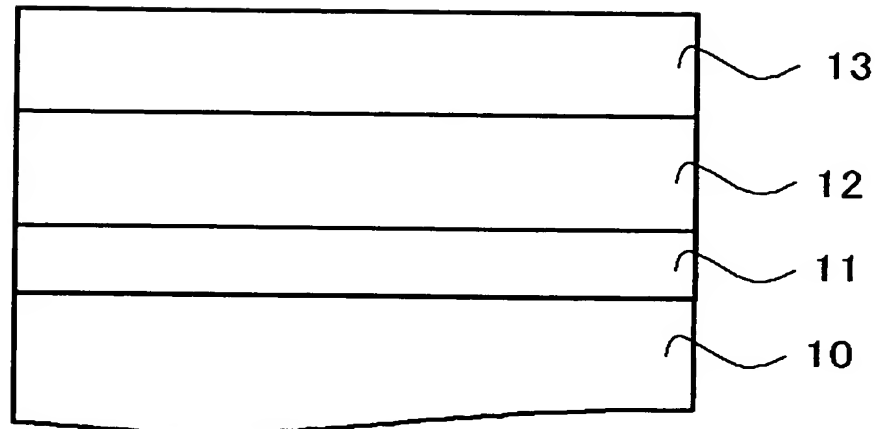
(e)



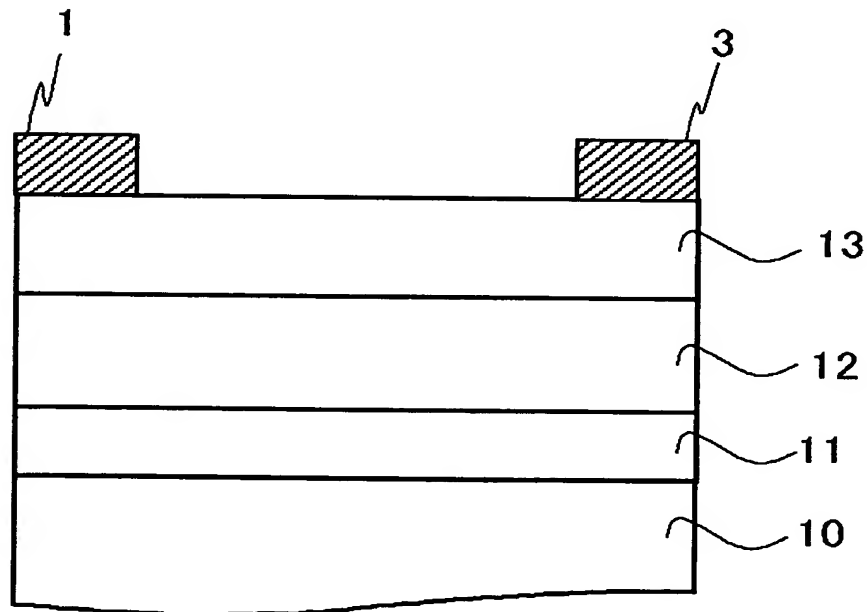
(f)

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FIG. 24



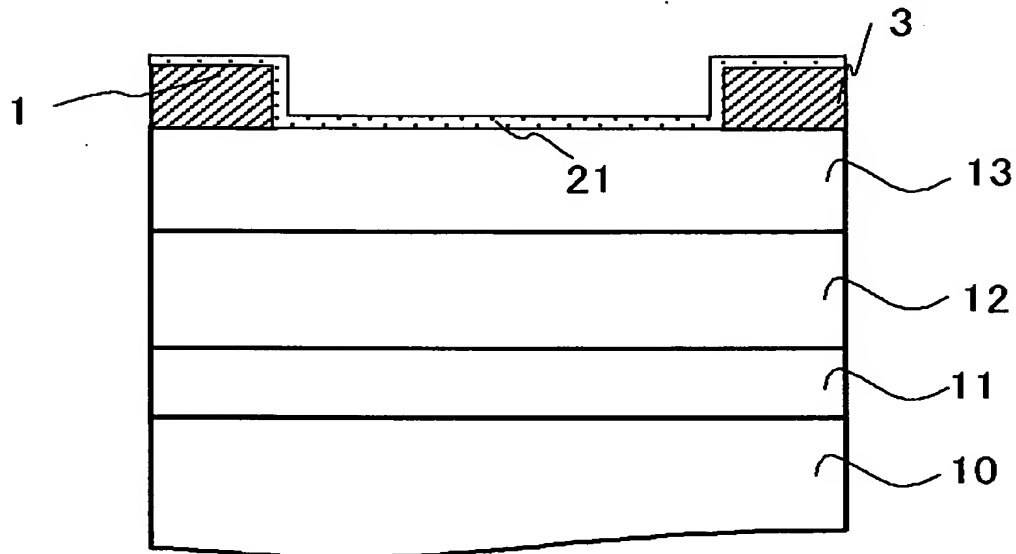
(a)



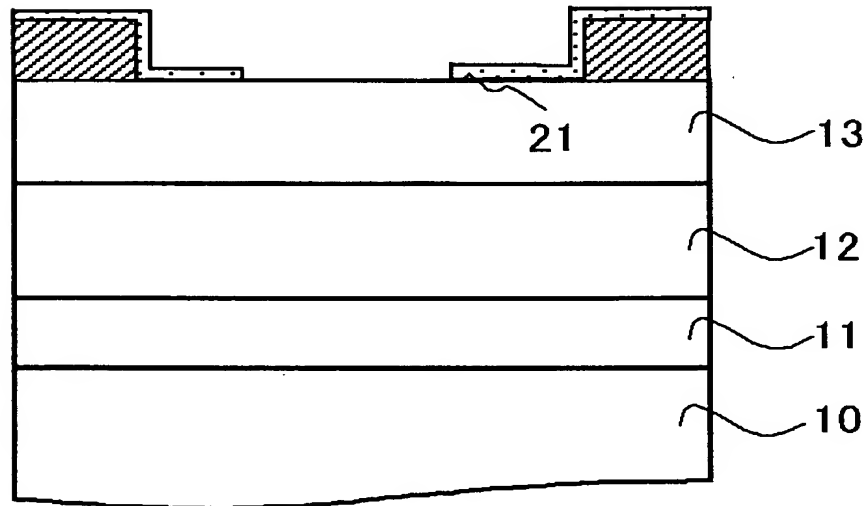
(b)

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FIG. 25



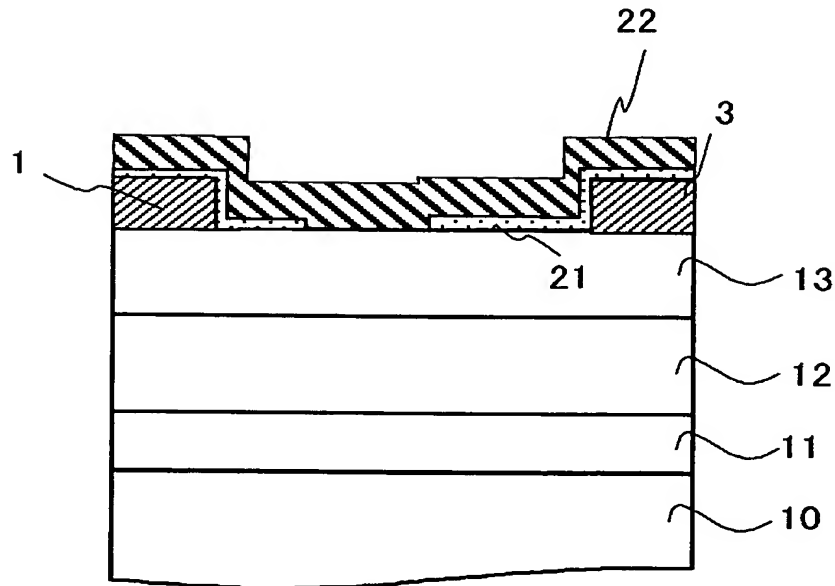
(c)



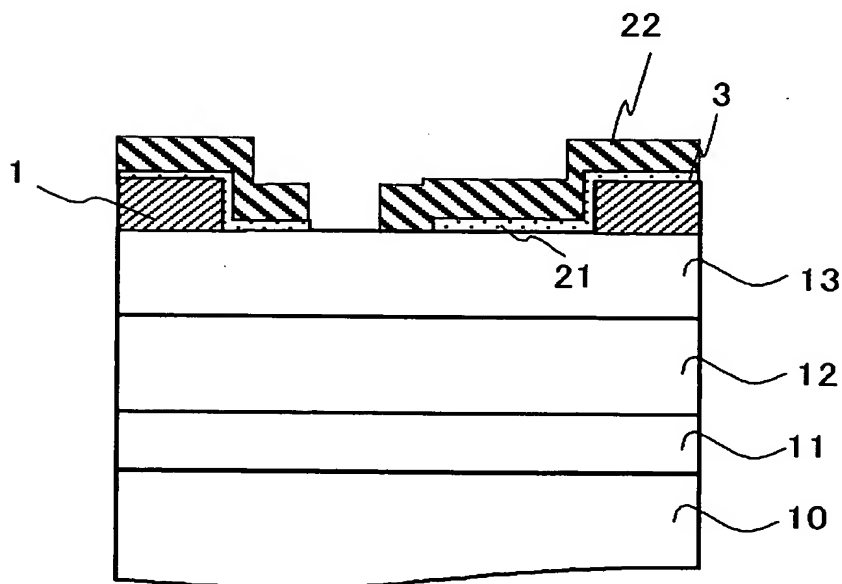
(d)

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FIG. 26



(e)



(f)

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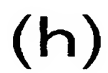
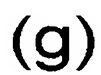


FIG. 28

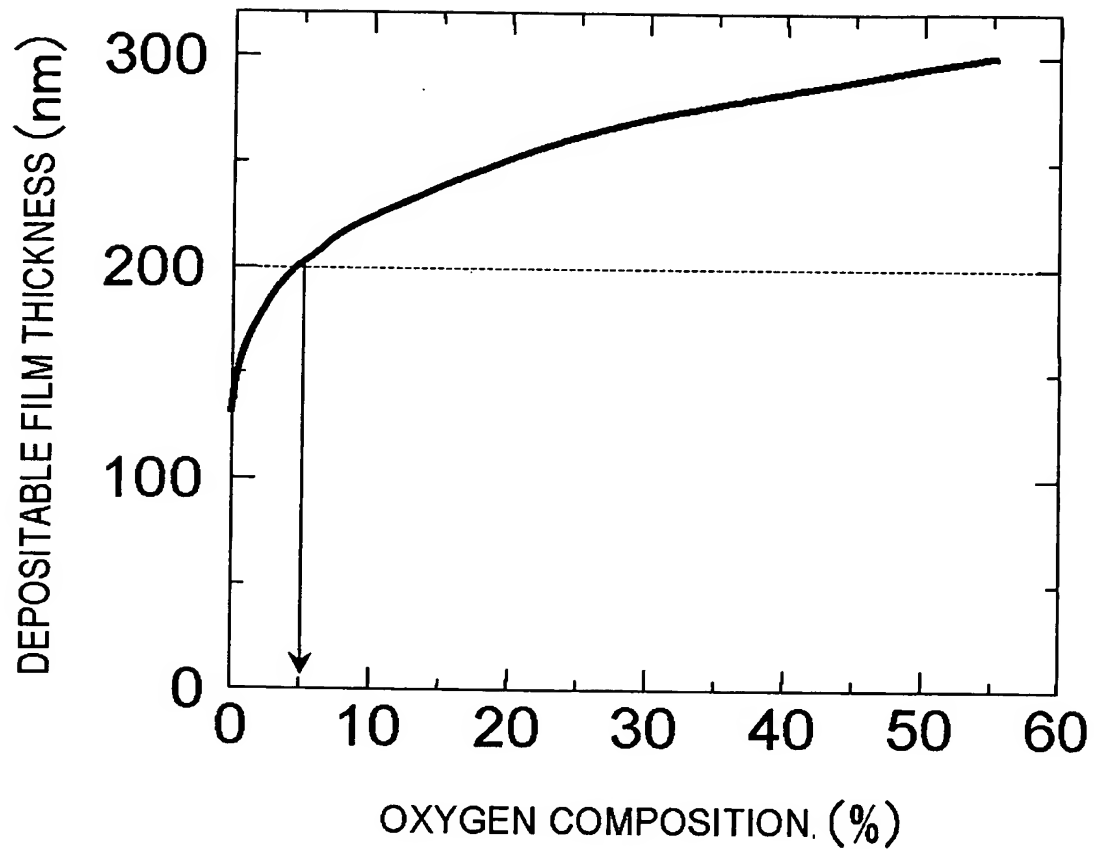
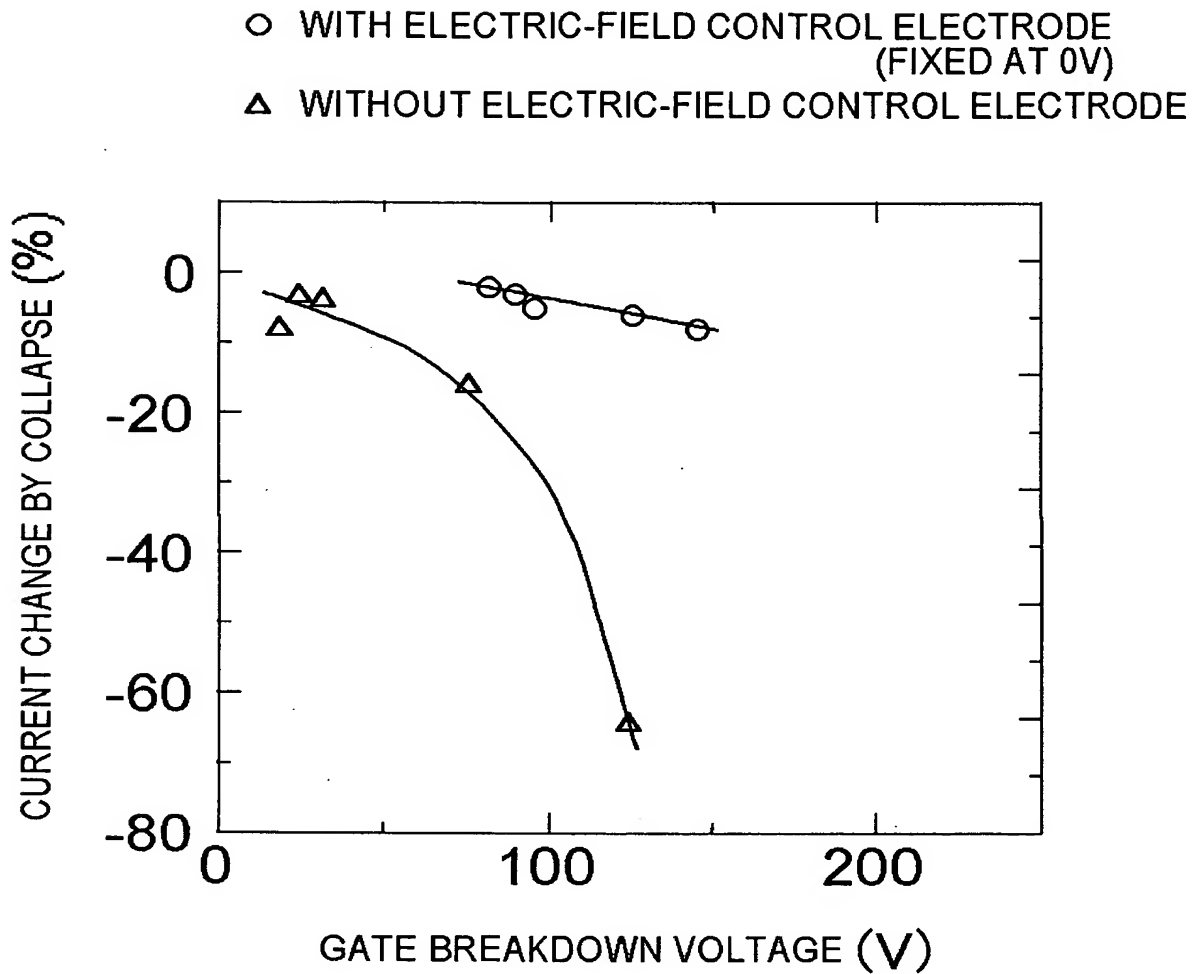




FIG. 29

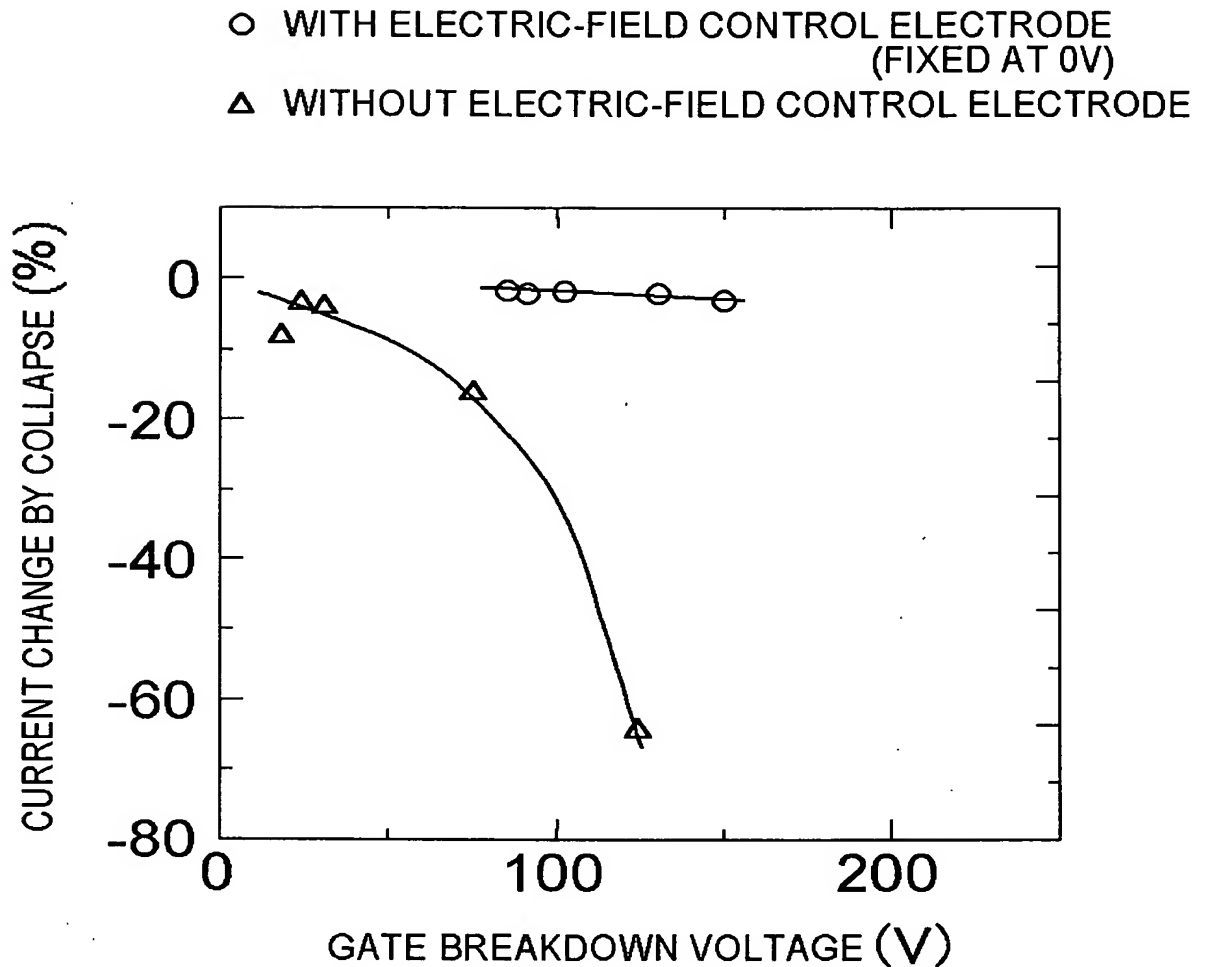


INSULATING FILM : SINGLE-LAYER OF SiN

SIZE OF ELECTRIC-FIELD CONTROL ELECTRODE : 0.5 $\mu$ m

DISTANCE BETWEEN GATE ELECTRODE  
AND ELECTRIC-FIELD CONTROL ELECTRODE : 0.5 $\mu$ m

FIG. 30

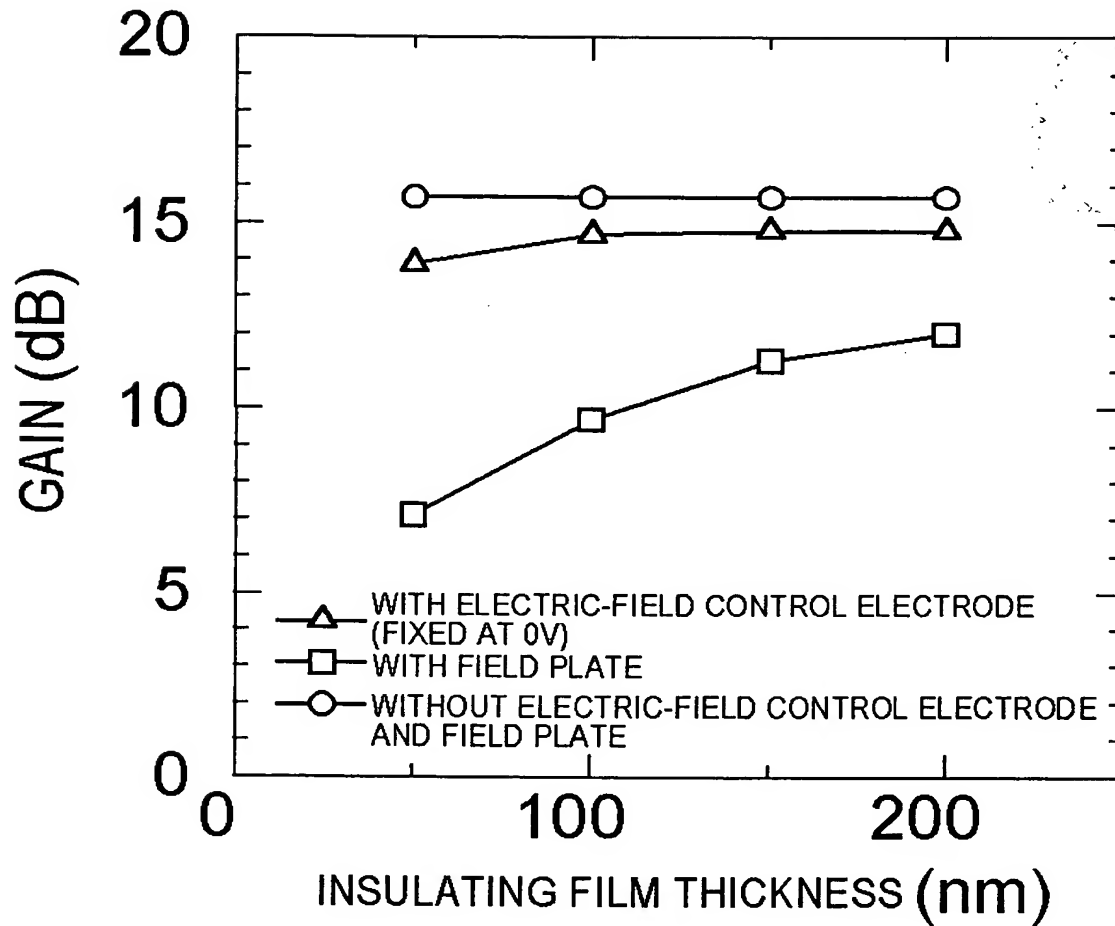


INSULATING FILM : SINGLE-LAYER OF SiN

SIZE OF ELECTRIC-FIELD CONTROL ELECTRODE :  $1.0\mu\text{m}$

DISTANCE BETWEEN GATE ELECTRODE  
AND ELECTRIC-FIELD CONTROL ELECTRODE :  $0.5\mu\text{m}$

FIG. 31



INSULATING FILM : SINGLE-LAYER OF SiN

FIELD PLATE LENGTH :  $1\mu\text{m}$

SIZE OF ELECTRIC-FIELD CONTROL ELECTRODE :  $0.5\mu\text{m}$

DISTANCE BETWEEN GATE ELECTRODE  
AND ELECTRIC-FIELD CONTROL ELECTRODE :  $0.5\mu\text{m}$